

10784377

Sheet 1 of 1

FORM PTO-1449 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY.DOCKET NO. 08425ZP	SERIAL NO. 10784377
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)		APPLICANT Richard Van Court Carr, et al..	
(37 CFR 1.98(b))		FILING DATE	GROUP

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U.S. PATENT DOCUMENTS

EXAMINER DATER	DOCUMENT NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
PK	2003	0	0	5	9	7	1	0	3/27/2003	Inoue	430	270.1	
PK	2002	0	0	0	4	5	7	0	1/10/2002	A. Zampini, et al.	528	257	2/23/2001
PK	2002	0	0	5	1	9	3	8	5/2/2002	Y. Maruda, et al.	430	270.1	9/7/2001
PK	2002	0	0	5	5	0	8	0	5/9/2002	G. N. Taylor, et al.	430	270.1	9/8/2001
PK	2002	0	0	6	1	4	8	4	5/23/2002	T. Arai, et al.	430	270.1	9/25/2001
PK	2002	6	2	9	1	1	3	0	9/18/2001	K. Kodama, et al.	430	270.1	7/27/1999
PK	2002	6	4	0	6	8	2	8	8/18/2002	C. R. Szmanda, et al.	430	270.1	2/24/2000

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
PK	JP	2 1 7 9 7 3 1	1/10/03	Japan (Abstract)			-X-	-X-
PK	WO	0 2 3 1 5 9 5	1/10/03	World	603F	7/00	X	
PK	EP	1 1 0 3 8 5 6	1/10/03	Europe	603F	7/039	X	
PK	EP	1 1 2 6 3 2 2	1/10/03	Europe	603F	7/039	X	
PK	WO	0 0 1 7 7 1 2	1/10/03	World	603F	7/039	X	
PK	WO	0 0 6 7 0 7 2	1/10/03	World	603F	7/004	X	
PK	WO	0 1 6 3 3 6 2	1/10/03	World	603F	7/00	X	
PK	WO	0 1 8 5 8 1 1	1/10/03	World	603F	214/00	X	
PK	WO	0 2 2 1 2 1 2	1/10/03	World	603F	7/004	X	
PK	WO	0 2 2 1 2 1 3	1/10/03	World	603F	7/004	X	
PK	WO	0 2 2 1 2 1 4	1/10/03	World	603F	7/004	X	
PK	WO	0 2 2 1 2 1 6	1/10/03	World	603F	7/039	X	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

PK	Hiroshi Ito, et al., "Synthesis and Evaluation of Alicyclic Backbone Polymers for 193 nm Lithography", American Chemical Society, 1998.
PK	Hiroshi Ito, et al., "Aliphatic Platforms for the Design of 157 nm Chemically Amplified Resists", SPIE Proceedings, Vol. 4690 (2002), 18-28.
PK	M. M. Chingra, et al., "Polymerization of 1,1,1-Trifluoroacetone with Aliphatic Secondary Amines. A Proton and Fluorine Magnetic Resonance Investigation," Organic Magnetic Resonance, Vol. 9, No. 1 (1977), pp. 23-28.
PK	H. E. Simmons, et al., "Fluoroketones" The Central Research Department Station, E. I. du Pont de Nemours and Co., Vol. 82 (1959), pp. 2288-2296.
PK	E. T. McBee, et al., "The Chemistry of 1,1,1-Trifluoropropane. II. The Reactions of 4-Methyl-1,1,1,5,5-hexafluoro-3-penten-2-one with Methylmagnesium Iodide," The Department of Chemistry, Purdue University (1958), pp. 4597-4598.
PK	A. L. Henne, et al., "Trifluoromethylated Butadienes," The Department of Chemistry at The Ohio State University (1954), pp. 5147-5148.
PK	K. J. Prysbyla, et al., "Hexafluoroacetone in Resist Chemistry: A Versatile New Concept for Materials for Deep UV Lithography," SPIE Advances in Resist Chemistry and Process IX Vol. 1672 (1992).
PK	M. K. Crawford, et al., "New Materials for 157 nm Photoresists: Characterization and Properties," SPIE Advances in Resist Chemistry and Processing IX Vol. 3999 (2000).
PK	R. R. Dammel, et al., "New Resin Systems for 157 nm Lithography," Journal of Photopolymer Science and Technology, Vol. 14 No. 4 (2001).
PK	H. Ito, et al., "Development of 157 nm Positive Resists," J. Vac. Sci. Technol. B 19(6) (2001).
PK	H. Ito, "Dissolution Behavior of Chemically Amplified Resist Polymers for 248-, 193-, and 157-nm Lithography," J. Res. & Dev. Vol. 45 No. 5 (2001).
PK	S. Cho, et al., "Investigation of a Fluorinated ESCAP based resist for 157 nm Lithography," (2001).
PK	K. Patterson, et al., "The Challenges in Materials Design for 157 nm Photoresists," Lithography, Solid State Technology, pp. 41-48 (2000).

EXAMINER

R. Karp

DATE CONSIDERED

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EXAMINER: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1449 (05/23/06)



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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

<p style="text-align: center;">INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(Use as many sheets as necessary)</i></p>				Complete If Known	
				Application Number	10/784,377
				Filing Date	02/23/2004
				First Named Inventor	Richard Van Court Carr, et al.
				Art Unit	1752
				Examiner Name	
Sheet	1	of	1	Attorney Docket Number	08425ZP USA

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FOREIGN PATENT DOCUMENTS

Examiner Initials ¹	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ²
		Country Code ³ Number ⁴ Kind Code ^{5,6} (e.g.)				
<i>ED</i>	WO 00/67072		11/09/2000	Du Pont		

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